SYSTEM AND METHOD FOR OPTIMIZING METROLOGY SAMPLING IN APC APPLICATIONS

Abstract

A system and method for optimizing metrology sampling rates in an advanced process control (APC) application. A method is provided for processing a run of workpieces, the method comprising the steps of: providing a database comprising subgroups of data representing characteristics from previously processed workpieces; selecting a first subgroup of data having characteristics that satisfy a predetermined criteria; determining processing conditions for a processing tool corresponding to said first subgroup of data; processing the run of workpieces with the process tool using the determined processing conditions; and measuring the run of workpieces according to a sampling rate determined from the first subgroup of data.